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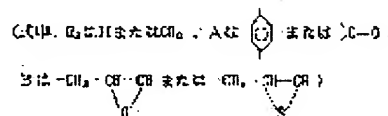
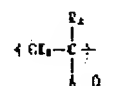
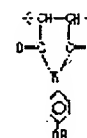
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## (54) ALKALI-DEVELOPING PHOTOSENSITIVE COMPOSITION

(57)Abstract:

**PURPOSE:** To provide such a photosensitive compsn. that can be developed with a water-base alkali soln. containing no org. solvent and has excellent development stability and sensitivity by incorporating an alkali-soluble copolymer containing specified monomers, photocation producing agent, and vinyl ether compd.

**CONSTITUTION:** This compsn. contains a monomer expressed by formula I, etc., monomer expressed by formula II, photocation producing agent, and vinylether compd. Thereby, a photocation polymerizing photosensitive compsn. is obtd. Since photosetting of this compsn. is not prevented by oxygen, a treatment to form an overcoat layer is not required. After exposure for an image, the compsn. can be developed with a water-base alkali developer and has excellent development stability and higher sensitivity. When this negative-type photosensitive compsn. is used for a printing plate, a water-base alkali developer for a positive-type planographic printing plate can be used for development.



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